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Plasma Techniques for Film Deposition (Hardback)

By Mitsuharu Konuma

Alpha Science International Ltd, United Kingdom, 2006. Hardback. Book Condition: New. 244 x 163 mm. Language: English . Brand New Book. Plasma Techniques for Film Deposition describes the technology and applications of cold plasma for thin-film deposition. The plasma is generated under low pressure and characterized by a non-thermal equilibrium. An attempt has been made to not only provide an introductory text but also to present the latest techniques and recent results. It offers fundamentals of plasma science such as its characterization, chemical and physical reactions in plasmas, basic techniques to generate and to diagnose plasmas. Techniques for generating high-density plasmas are outlined like the conventional electrical and magnetic methods, and the modern schemes for inductively coupled and helicon-wave plasmas. It includes plasma diagnostic methods, such as optical spectroscopy, electrical probes, mass and energy analysis of excited molecules and ions in plasma. Specific techniques are treated for thin-film formation: sputter deposition, ion plating, plasma enhanced chemical vapor deposition and plasma surface modification. Films, like amorphous, nano- and micro-crystalline silicon, polymorphs of carbon, i.e. amorphous phase, diamond, fullerenes and nanotubes, boron and carbon nitrides can be deposited.



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